

ABSTRACT

A substrate processing apparatus, comprising: a processing chamber which provides a space for flowing desired gas and for depositing a desired film on a substrate; a lamp unit group having at least one lamp unit which is disposed in the processing chamber and which includes a filament for heating the substrate and a lamp tube surrounding the filament; at least first and second casings which surround the lamp unit, the first casing surrounding the lamp unit and the second casing surrounding the first casing; and a refrigerant flowing apparatus for flowing cooling medium to a first space formed between the lamp unit and the first casing, and to a second space formed between the first casing and the second casing, is disclosed.